

L Number	Hits	Search Text	DB	Time stamp
1	25	wafer and 204/263.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 13:59
2	14	wafer and 204/263.ccls. AND diffus\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 15:39
3	9	wafer and 204/263.ccls. AND diffus\$5 AND membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 15:39
4	1628	wafer AND diffuser	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 15:40
5	205	wafer AND diffuser AND membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 15:43
6	30	wafer AND diffuser AND membrane AND 204/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 15:52
7	33	204/271.ccls. and membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:03
8	196	204/271.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:26
9	511	diffuser near5 membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:27
10	50620	diffuser near5 membrane same plating or electroplating	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:27
11	16	diffuser near5 membrane and 204/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:41
12	85	diffuser ADJ membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:47
13	2	diffuser ADJ membrane AND 118/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:46
14	85	diffuser ADJ membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:46
15	34578	diffuser ADJ membrane and workpiece or work adj piece	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:47
16	1	diffuser ADJ membrane and workpiece	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:48
17	2	diffuser ADJ membrane and work adj piece	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/16 18:48